

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Cohen, et al.

Serial No.: 09/206,027

Confirmation No.: 4950

Filed: December 4, 1998

**For: Plasma Preclean With
Argon, Helium, and
Hydrogen Gases**

Group Art Unit: 1765

Examiner:

Unit: 1765

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GROUP 1700

Official

Assistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

**CERTIFICATE OF FACSIMILE
TRANSMISSION UNDER 37 CFR 1.8**

I hereby certify that this correspondence and the documents referred to as attached therein are being facsimile transmitted to the U.S. Patent and Trademark Office to the fax number indicated by the Examiner, namely, Lan Vinh, fax number 703-872-9310 to the attention of the named Examiner, on the date below.

3/15/02
Date

Robert D. Edwards
Signature

RESPONSE TO OFFICE ACTION DATED NOVEMBER 20, 2001

In response to the Office Action dated November 20, 2001, having a shortened statutory period for response extended one-month to expire on March 20, 2002, please enter the following amendments and reconsider the claims pending in the application for reasons discussed below. The Commissioner is authorized to charge \$348.00 for two additional independent claims and ten total additional claims to Deposit Account No. 20-0782/AMAT/3049.X1/CPES/DT/BTP, along with any other fees to make this response timely.

IN THE CLAIMS:

Please add the following new claims 31-40:

1. A method for processing a substrate in a processing chamber, comprising exposing a patterned substrate surface to a plasma generated from a gas mixture consisting of argon, helium and hydrogen, wherein the gas mixture comprises less than about 75% by volume of argon.

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